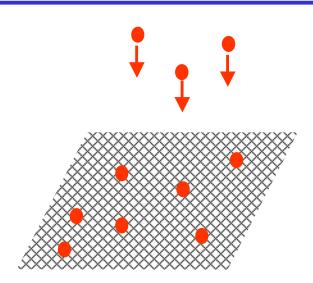
Applications of kinetics to surface science and simulations of epitaxial growth

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Statistical physics approach: discrete models



Why kinetic Monte Carlo? two reasons:

- technical
- physical (external time scale comes into play)

Ising

$$E = -\sum_{j \le k} J_{ik} S_i S_k - H \sum_j S_i$$
$$S_i = \pm \frac{1}{2}$$

(simple) lattice gas

$$E = \sum_{j < k} V_{ik} n_i n_k + E_s \sum_j n_i$$

$$n_i = 0,1$$
mapping $n_i \leftrightarrow S_i + \frac{1}{2}$

(N-states) Potts model

$$E = -\sum_{j < k} J_{ik} \delta_{S_i S_k}$$

Why kinetic Monte Carlo ? (I)

- Transition probabilities $W(i,j)/W(j,i) = \exp(-\Delta E/kT)$
- There is only a finite number of ΔE 's rate constants can be precomputed an stored in a 'class table' (saves frequent evaluations of exp function)
- At low T, in the Metropolis algorithm, most of the transitions will be rejected → simulation becomes inefficient
- solution: N-fold way
 - build a complete class table
 - use a random number to select a class, proportional to the transition probability of that class (the acceptance of this step is 100%!)
 - execute one process (spin flip) from the selected class
 A. B. Bortz, M. H. Kalos and J. L. Lebowitz, J. Comp. Phys. 17, 10 (1975)

Why kinetic Monte Carlo? (II)

Topics to be studied

- Systems in a metastable non-equilibrium state: relative time scales of different relaxation processes must be represented correctly.
- absolute time scale set by external process (e.g. deposition and/or desorption)

Required features of the algorithm

- The ratio of the "forward" and "backward" probabilities must equal the ratio of "forward" and "backward" rate constants (detailed balance condition; it must be fulfilled by all Monte Carlo methods).
- Strict proportionality between the probability of selecting any process and its rate constant.
- one-to-one mapping between "simulation time" and "physical time".

Topics of kinetical simulations

Surface science

- lattice-gas Hamiltonian
- temperature-programmed desorption spectra
- order-disorder phase transitions in adsorbate layers
- surface diffusion
- surface reactions / heterogeneous catalysis

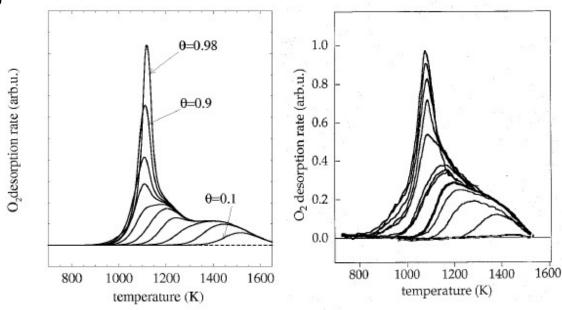
Epitaxial growth simulations

- SOS model of the crystal
- the roughening transition
- dynamical roughening
- sub-monolayer growth:
 - growth mode transition from step flow to island growth
 - scaling relations in island growth
- ripening phenomena

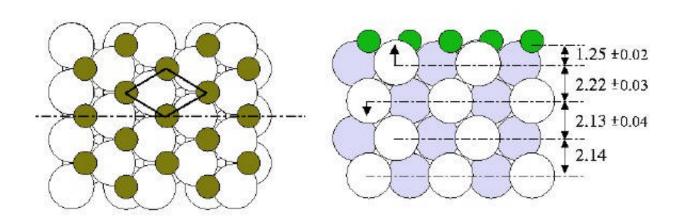
Some applications in Surface Science

Temperature-programmed desorption

- atoms adsorbed on a surface
- interaction between atoms adsorbed in neighboring sites
 - \rightarrow binding energy depends on coverage Θ
- substrate is heated with a constant rate (typically between 0.1 K/sec and 10 K/sec), thereby desorbing particles from the surface
 - → kinetics enters



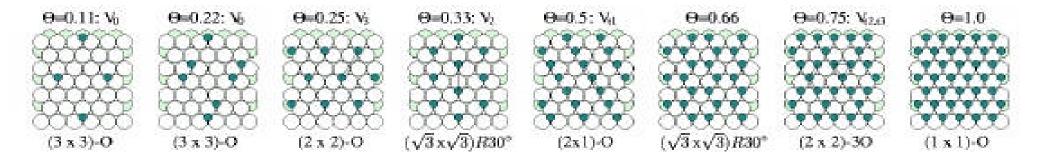
Lattice-gas Hamiltonian

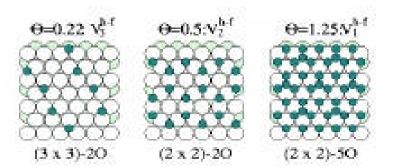


$$H = E_s^{\text{hep}} \sum_{i} n_i + E_s^{\text{fee}} \sum_{i} n_i + V_{1n}^{\text{hep}} \sum_{i,a} n_i n_{i+a} + V_{1n}^{\text{fee}} \sum_{i,a} n_i n_{i+a} + V_{1n}^{\text{fee}} \sum_{i,a} n_i n_{i+a} + V_{1n}^{\text{hep}-\text{fee}} \sum_{i,a'} n_i n_{i+a'} + V_{2n}^{\text{hep}} \sum_{i,b} n_i n_{i+b} + V_{2n}^{\text{fee}} \sum_{i,b} n_i n_{i+b} + V_{2n}^{\text{hep}-\text{fee}} \sum_{i,b'} n_i n_{i+b'} + V_{3n}^{\text{hep}} \sum_{i,c} n_i n_{i+c} + V_{3n}^{\text{fee}} \sum_{i,c'} n_i n_{i+c'} + V_{\text{trio}} \sum_{i,a,a'} n_i n_{i+a} n_{i+a''} + \dots$$

Determining the parameters of the Hamiltonian

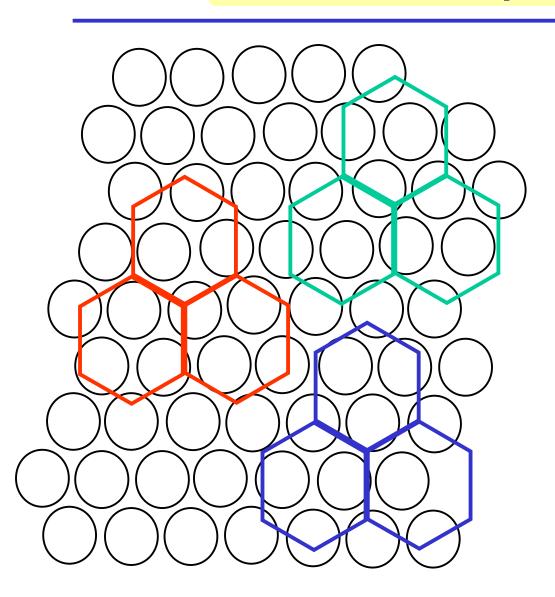
The energy of numerous ordered structures must be determined (e.g. by DFT calculations). Then a system of linear equations for the parameters is set up and solved.





C. Stampfl et al., Phys. Rev. Lett. **83**, 2993 (1999).

Order-disorder phase transitions



- adsorbate layer may form an ordered sublattice
- registry of the sublattice w.r.t. the substrate defines a multi-values order parameter (N-states Potts model)
- quenching below the transition temperature leads to domain wall formation
- domain growth as a function of time shows power law scaling

Surface diffusion

- diffusion constant D= $K_{th} \Gamma$
- tracer diffusion: only Γ is relevant
- thermodynamic factor is an equilibrium property

$$K_{th} = \left(\frac{d\mathsf{m}}{dn}\right)_{T} = \left(\frac{dn}{d\mathsf{m}}\right)_{T}^{-1} = \mathsf{C}_{T}^{-1}$$

- hopping rate Γ obtainable from kinetic Monte Carlo simulations, using the relation $\Delta x = 4 a^2 \Gamma t$ (for a square lattice)
- dynamical correlations important (e.g. in vacancy-assisted diffusion)
- chemical diffusion in kMC: analyse decay of density profile, starting with a given distribution (e.g. Gaussian) of particles.

Kinetic simulations in epitaxy

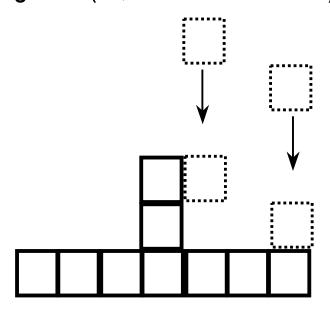
A.-L. Barabasi and H.E. Stanley, Fractal Concepts in Surface Growth, Cambridge University Press, 1995

J. Venables et al., Rep. Prog. Phys. **47**, 399 (1984); R. M. Tromp and J. B. Hannon, Surf. Rev. Lett. **9** 1565 (2002).

Simple discrete models of interface dynamics

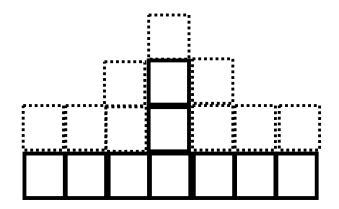
ballistic deposition model:

particles stick as soon as they find a neighbor (or, likewise an NNN)



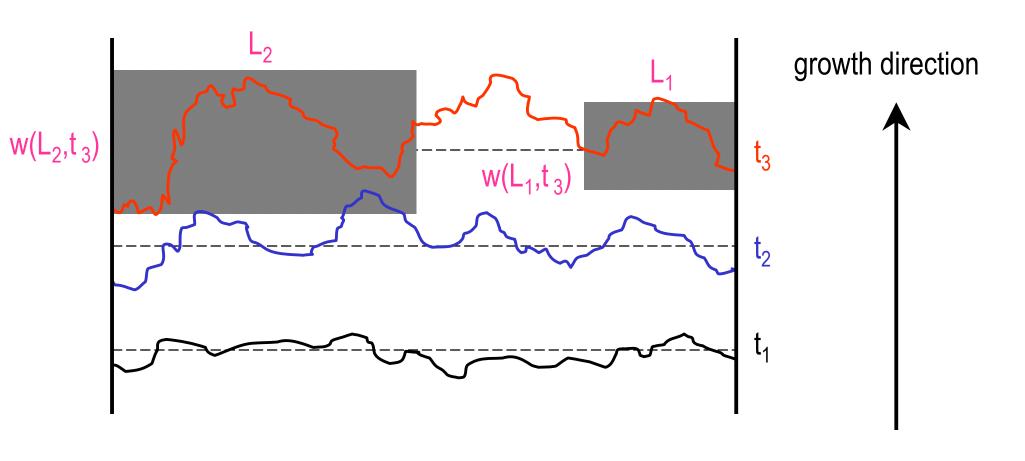
Eden model:

sites where the new particles will have a neighbor get occupied randomly (with equal probability, or some modification thereof)



continuum model: Kardar-Parisi-Zhang equation

Scaling of surface roughness



 $w(L,t) = L^{\alpha}$

small times: w(L,t) = t

larger times: $w(L,t) = t^{\beta}$

crossover time = L^z

Solid-on-Solid (SOS) models

General feature of SOS models:

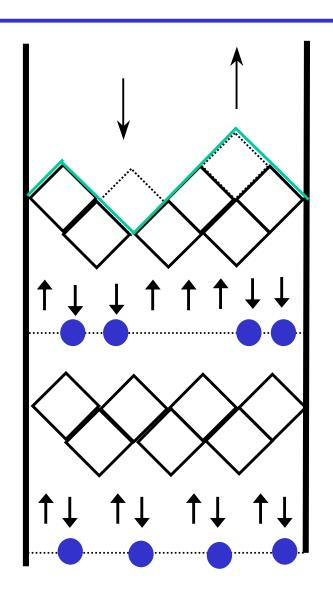
- no voids
- no overhangs

"single-step" model:

adsorption and desorption at local minima / maxima

equivalence to Ising model or lattice gas model exponents in 1+1 dimensions:

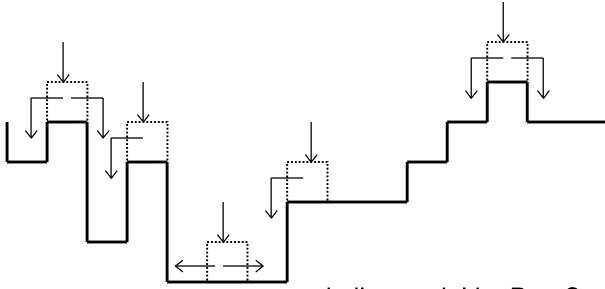
$$\alpha = \frac{1}{2}$$
 $\beta = \frac{1}{3}$



MBE: models with transient diffusion

Wolf-Villain model:

randomly deposited particles have transient mobility: they move to the neighboring sites(s) with highest coordination



similar model by Das Sarma-Tamborenea

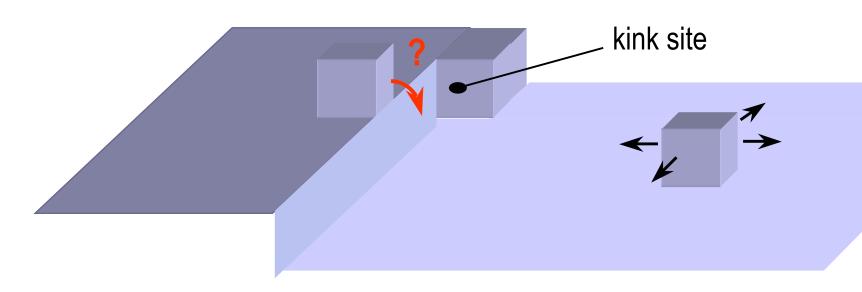
MBE: models with activated diffusion

Schwoebel-Ehrlich effect

$$\Gamma = \Gamma_0 \exp(-(E_A + E_s)/kT)$$

hopping diffusion

$$\Gamma = \Gamma_0 \exp(-E_A/kT)$$



simplest model: atoms with at least one in-plane neighbor are immobile (irreversible attachment)

nucleation theory

assumption: only single atoms are mobile, larger clusters with i > 1 atoms immobile

idea:

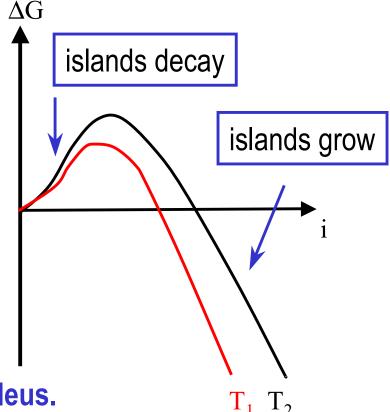
We can ascribe a chemical potential μ_i to each particle in a cluster of i atoms. Consider equilibrium $N_i + N_1 \longleftrightarrow N_{i+1}$ Then, for all $i \Rightarrow \mu_i = i \mu_1$

non-equilibrium:

 $\mu_1(p,T)$ is fixed externally (supersaturation due to incoming flux),

$$\Delta G = \mu_i - i \mu_1$$

Maximum of DG defines the critical nucleus.



island density: scaling laws

coupled hierarchy of rate equations

$$\frac{dN_1}{dt} = R - \frac{N_1}{t} - 2DS_1N_1^2 - \sum_{i=2}^{\infty} DS_iN_1N_i$$
deposition evap. nucleation attachment

$$\frac{dN_i}{dt} = DS_{i-1}N_{i-1}N_1 - DS_iN_iN_1$$
i-1

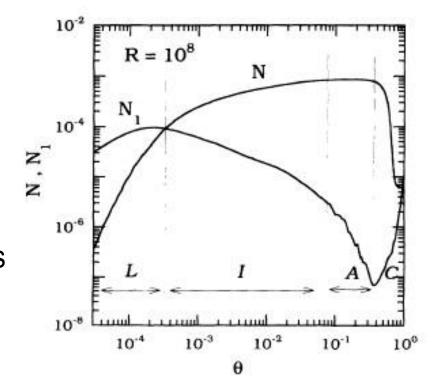
$$N_x \sim \left(\frac{R}{D}\right)^{ic+2}$$

discussion for critical island size i_c=1

• evaporation neglected: $\frac{dN_1}{dt} = R - 2DS_1N_1^2 - DS_iN_1N$

$$N = \sum_{j=2}^{\infty} N_j \qquad \frac{dN}{dt} = DS_1 N_1^2$$

- very short times: R dominates! $N_1 = Rt$; $N = S_1 R^2 D t^3$
- medium times: no new nucleation, flux is consumed by attaching to existing islands $N_I \sim R/(D S_i N); \qquad N \sim (3t)^{1/3}; N_I \sim R^{2/3} D^{-1/3} t^{-1/3}$



simple treatment of i_c>1

islands with i > i_c are stable and are treated with a single variable

$$N_x = \sum_{j=i_c+1}^{\infty} N_j$$

• only two eq.s remain: $\frac{dN_1}{dt} = R - \frac{N_1}{t} - \frac{d(w_x N_x)}{dt}$

$$\frac{dN_x}{dt} = DS_{i_c}N_{i_c}N_1 - \underline{U_c} \text{ loss term due to}$$
coalescence

 $U_c = 2N_r dZ/dt$

- saturation of island density for i_c=1:
 - equate $Ds_I N_I^2$ and U_c : $N_x = N_I^2$
 - insert into eq. (1): $Ds_1N_1^3 = R$
 - use medium-time-scale relation $N_x = 1/N_1$
 - result: $N_x \sim (D/R)^{1/3}$

kMC simulations of the SOS model

- simulation on a grid, associate potential minima with grid points
- classification of initial and final state by 'atomic neighborhoods'
 e.g., the number and relative position of neighbors

could define the class

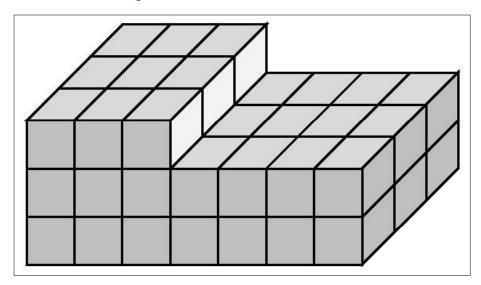
- classify possible transitions W(f,i) from i to f, each class k is characterized by a rate (input to the simulation). concerted events (simultaneous motion of several atoms) can be accounted for
- detailed balance (ensures that thermal equilibrium is reached) $W(i,j)/W(j,i) = \exp(-(G_i G_i)/kT)$

bond-counting models

- Let's assume that the energy at the transition state is equal for all transitions
- Let the binding energy E_i be a function of the number of neighbors (Kossel crystal).
- Let all prefactors be equal.

$$\Gamma^{(j)} = \Gamma_0 \exp(-f(n)/kT)$$

specific models for f(n):



metal:

$$f(n) = A \sqrt{n} + B n$$

semiconductor:

$$f(n) = E_S + n E_B$$

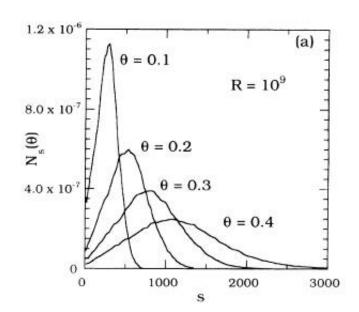
Island distributions: scaling

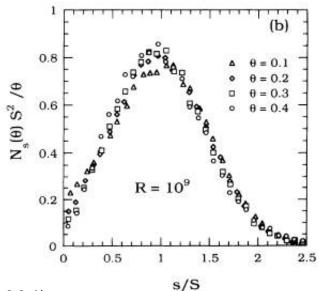
$$Z = \sum_{j \ge 2}^{\infty} j N_j$$

$$N = \frac{Z}{N_x} = \frac{\Theta - N_1}{N_x}$$

Provided that there is only a single length scale in the problem (the diffusion length, or the average island size N), the island size distribution displays scaling:

$$N_{j} = G(\Theta, N) f\left(\frac{j}{N}\right) \propto \frac{\Theta}{N^{2}} f\left(\frac{j}{N}\right)$$

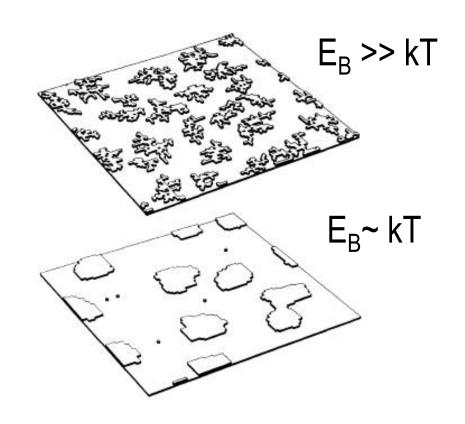




J.G. Amar, F. Family & P.M. Lam, Phys. Rev. B 50, 8781 (1994)

island distributions: scaling

- bond-counting model, reversible attachment
- islands are not fractal, but compact
- scaling property of the island density still valid, but scaling function is different for reversible and irreversible case

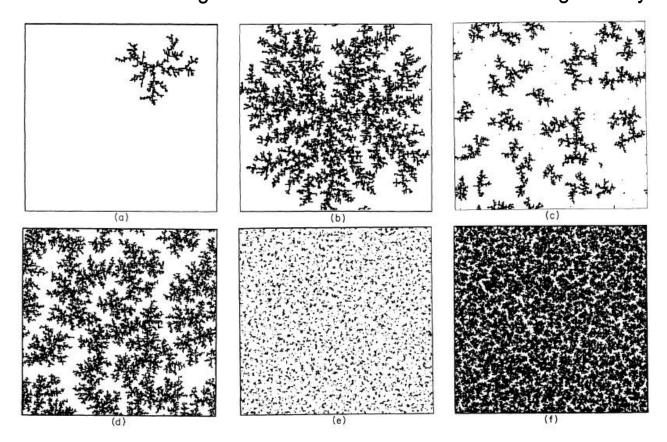


C. Ratsch, A. Zangwill, P. Smilauer and D.D. Vvedensky, Phys. Rev. Lett. **72**, 3194 (1994)

Island growth (including diffusion of islands)

diffusion low: single fractal island

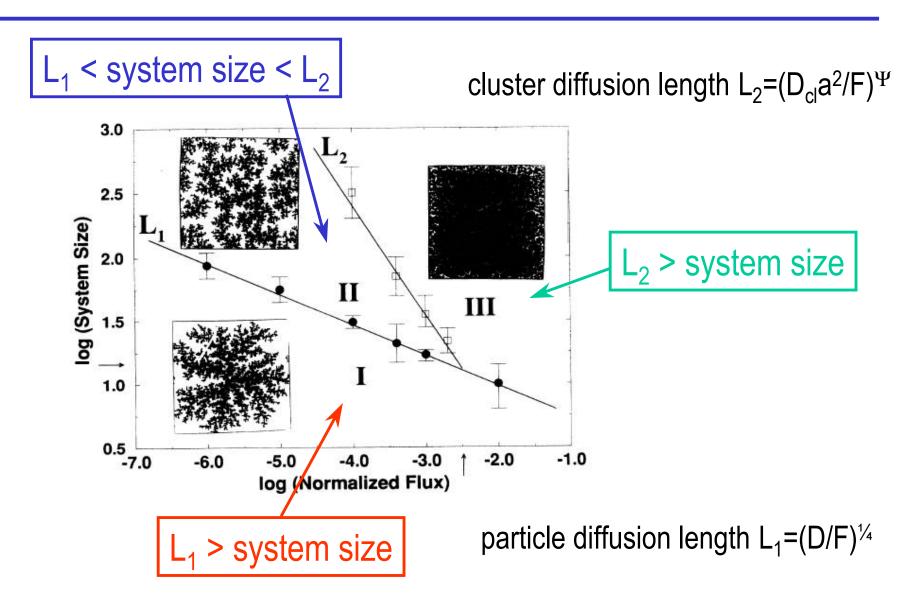
diffusion high: many fractal islands



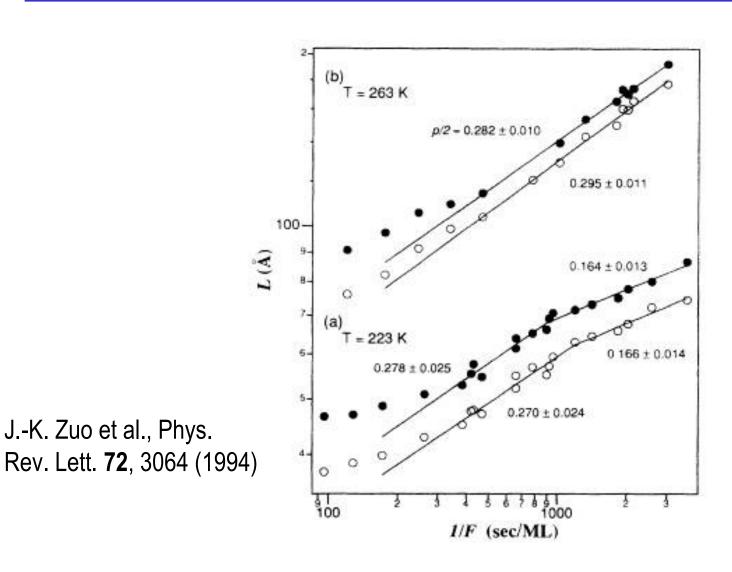
percolating network of fractal islands

diffusion along island edges: compact islands, ordinary percolation transition

Scaling regimes

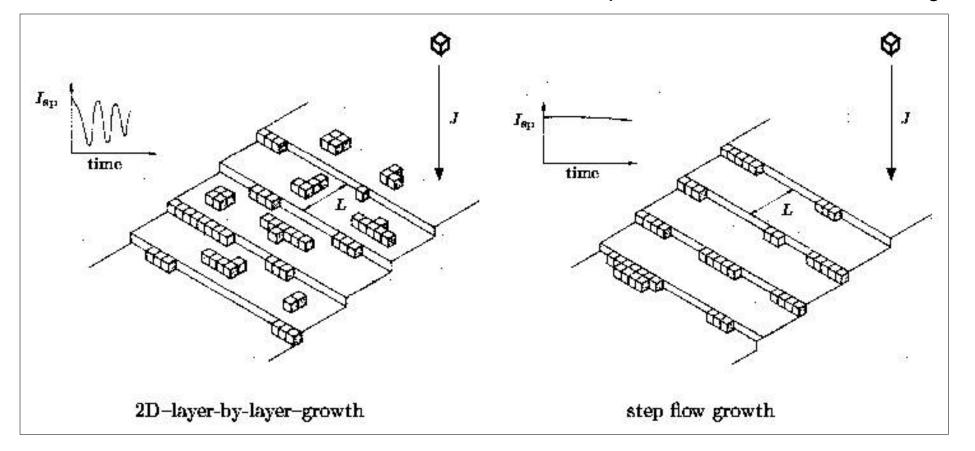


Experimental test: Cu on Cu(001)



Diffusion and the onset of step-flow growth

 $D = \lambda^2/4\tau$; $\tau^{-1} = Ra^2$ mean time between two depositions; λ : diffusion length



growth mode transition at $\lambda = L$?

J. H. Neave et al., Appl. Phys. Lett. 47 (1985), 100

Ripening Phenomena

Set of rate equation with quasi-continuous indices (island radii) of the variables (island size distribution) $N_j(t) \rightarrow f(r,t)$ partial differential equation $\frac{\partial f(r,t)}{\partial t} + \frac{\partial}{\partial r} [\dot{r}(r,t)f(r,t)] = 0$

scaling solution (for material transport by surface diffusion)

$$r^*(t) = r^*(0) \left(1 + \frac{t}{t_0}\right)^{1/4}$$
 Without external flux, islands 'cannibalize each other!
$$f(r,t) = g\left(\frac{r}{r^*(t)}\right) / \left(1 + \frac{t}{t_0}\right)$$

I.M. Lifshitz & V.V. Shlezhov, J. Phys. Chem. Solids 19, 35 (1961).

B. K. Chakraverty, J. Phys. Chem. Solids 28, 2401 (1967).

Algorithms for kinetic Monte Carlo

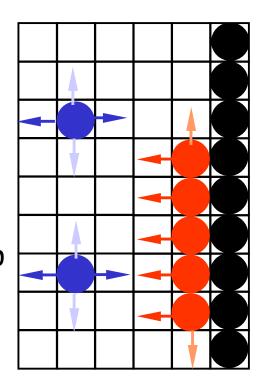
- While being aware of all possible processes at an instant of time, we need a way of stochastically selecting one process.
- An internal clock keeps track of the advancement of physical time.
 - If the processes are clearly separated in time, i.e. processes are uncorrelated on the time scale during which the processes takes place), the waiting time for each individual process has Poissonian distribution
 (K. A. Fichthorn and W.H. Weinberg, J. Chem. Phys. 95, 1090 (1991))
- We need to update the list of possible processes according to the new situation after the move.

Specific algorithms:

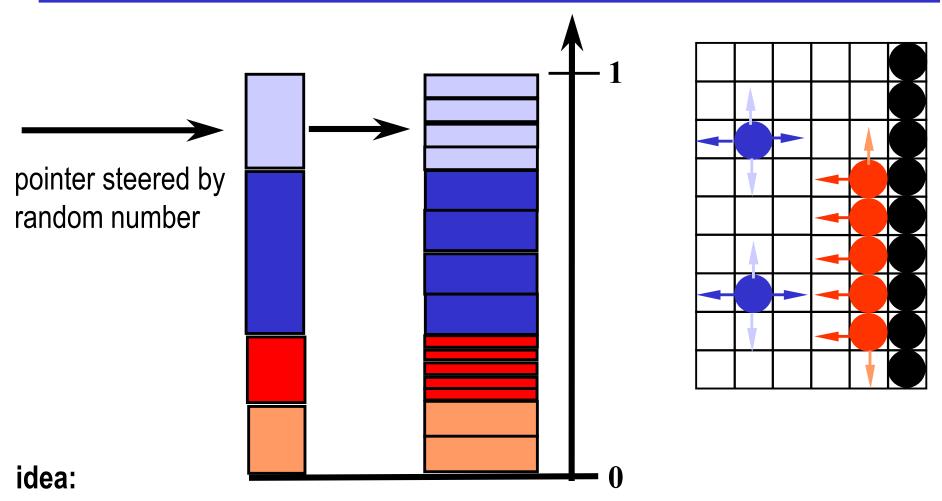
- process-type list algorithm
- binary-tree algorithm
- time-ordered-list algorithm

First thoughts

- example: lattice L_x x L_y
- fool's algorithm: first select one particle, then select one move of that particle
- the correct solution: cumulated partial rates $r_k = \sum_{i=1}^k \Gamma_i$, normalized to the total rate $R = r_N$
- selection process: draw a random number ρ and compare it to all the r_k/R sequentially; as soon as ρ exceeds r_k/R , execute process k
- problem: we need to compare ρ to many (in the worst case all) of the r_k/R
- note: Selecting a process with the right probability requires that we can enumerate all N processes.

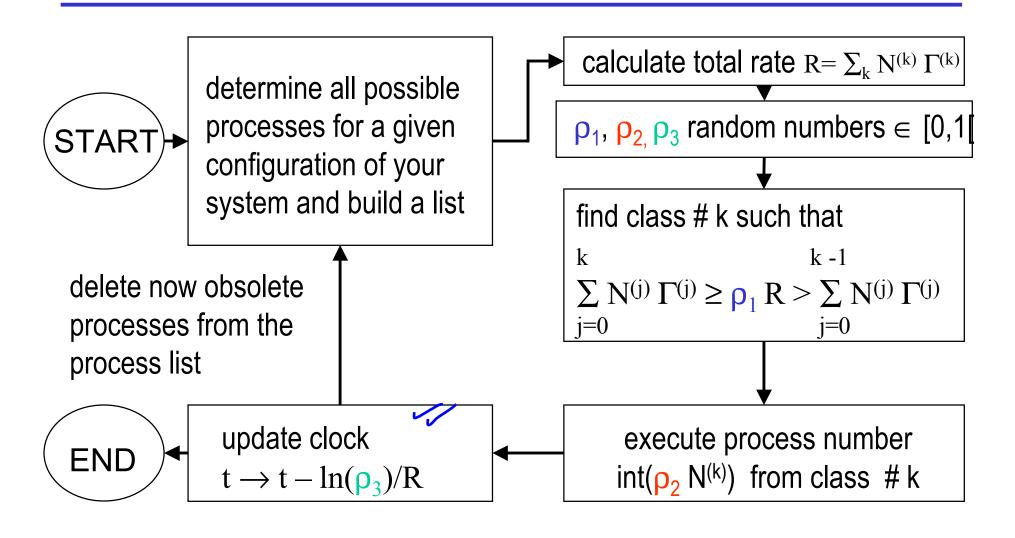


Process-type-list algorithm



for p process types, we need to compare only to the p numbers $N^{(k)}$ $\Gamma^{(k)}$, k=1,p, rather then to **all** r_k/R (which are much more numerous)

flow chart for process-type-list kMC



Local updating in the process-type list

process type	1				2			
# in type	1	2	3	4	1	2	3	4
from	(2,3)	(2,3)	(i,j)	(i,j)	(2,3)	(2,3)	(i,j)	(i,j)
to	(1,3)	(3,3)	(i-1,j)	(i+1,j)	(2,4)	(2,2)	(i,,j-1)	(i,,j+1)
# at its site	1	3	1	3	2	4	2	4

(i,j)

double-entry accounting: Tables attached to the lattice sites tell us which processes to delete from the process list!

(2,3)

# at site	ptype	# in type	
1	1	1	
2	1	2	
3	2	1	
4	2	2	

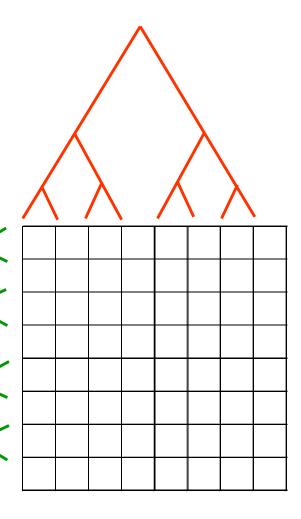
X)	$\times \times \times \times \times \times$		
8	# at site	ptype	# in type
8	1	1	3
	2	1	4
	3	2	3
	4	2	4

Binary (or quaternary) tree

simulation area L x L, L=2ⁿ

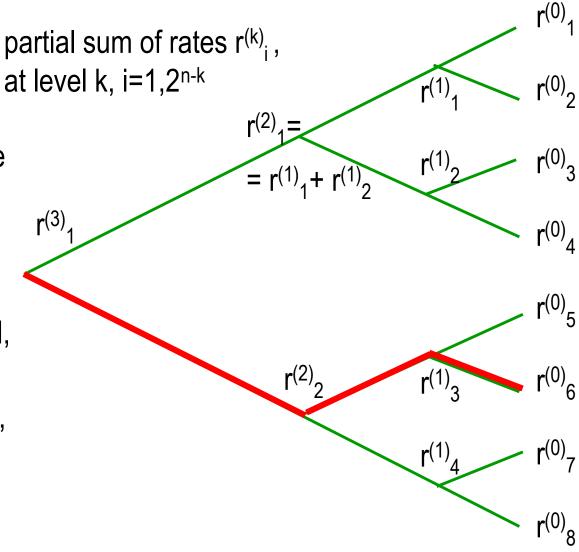
idea:

use the real-space tree structure for a partitioning of the cumulative partial rates

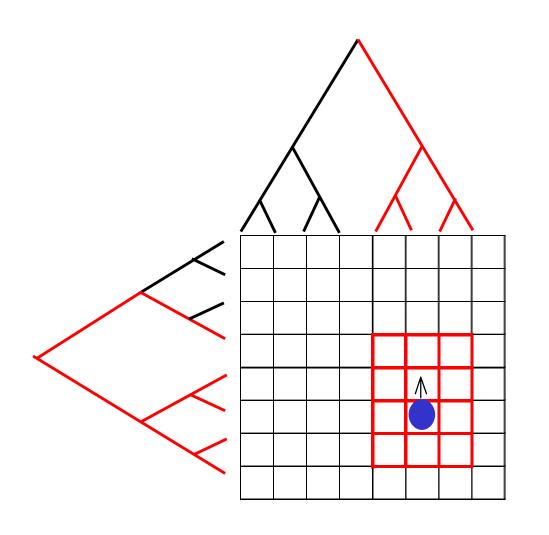


Selecting a process from the tree

- generate a random number ρ'
- normalize to the total rate $R=r^{(n)}_1$, $\rho=\rho'/R$
- run through the tree from left to right, if $\rho < r^{(k)}_i$, branch upward, else branch downward and replace $\rho \to \rho r^{(k)}_i$,



Local update in the binary tree



Since the arrangement of partial sums of rates reflects the lattice topology, the update only affects few 'branches' of the tree (selective update).

Time-ordered list algorithm

- assign a random waiting time t_i to each individual process
- sort all processes according to ascending waiting time (requires only log(N) comparisons, if done in a way similar to the binary tree)
- always select the first process and execute it
- advance the clock by $t \rightarrow t + t_i$
- this algorithm requires many exponentially distributed random numbers; thus it's advisable to use specially a designed random number generator

B. Lehner, M. Hohage & P. Zeppenfeld, Chem. Phys. Lett. 336, 123 (2001)